

FIG. 1

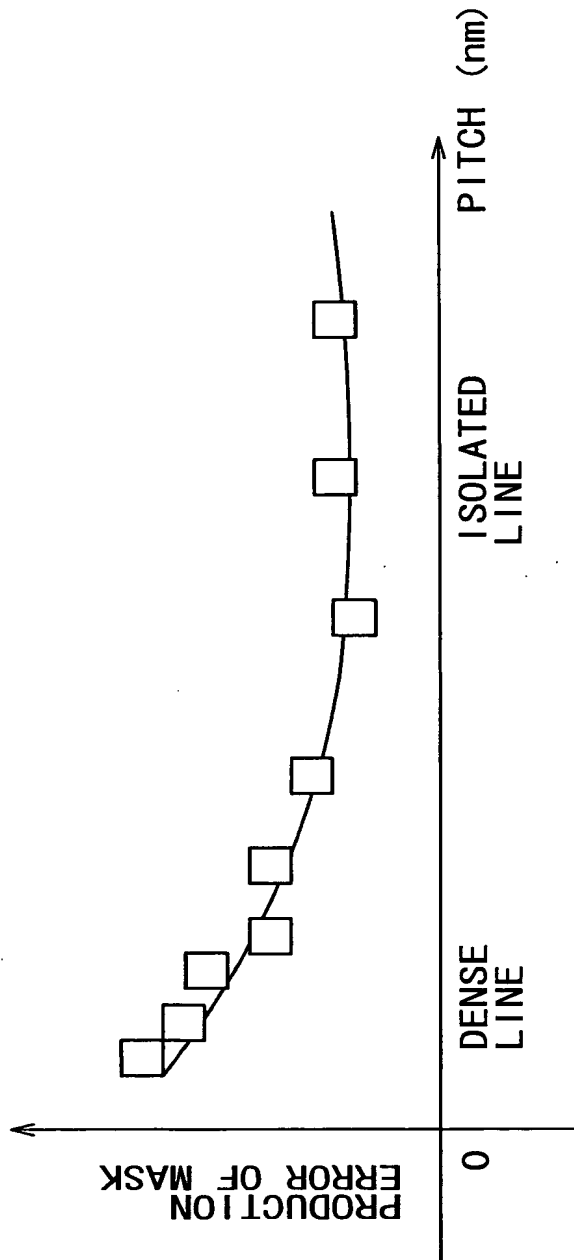


FIG. 2

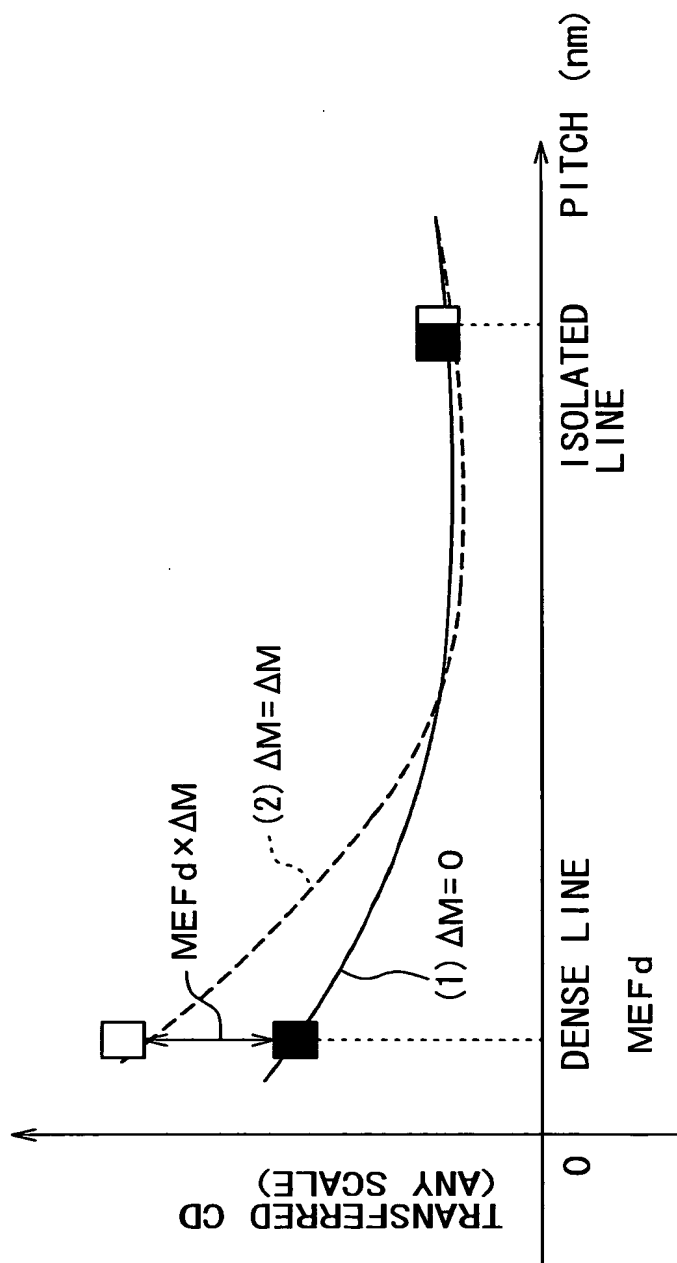


FIG. 3

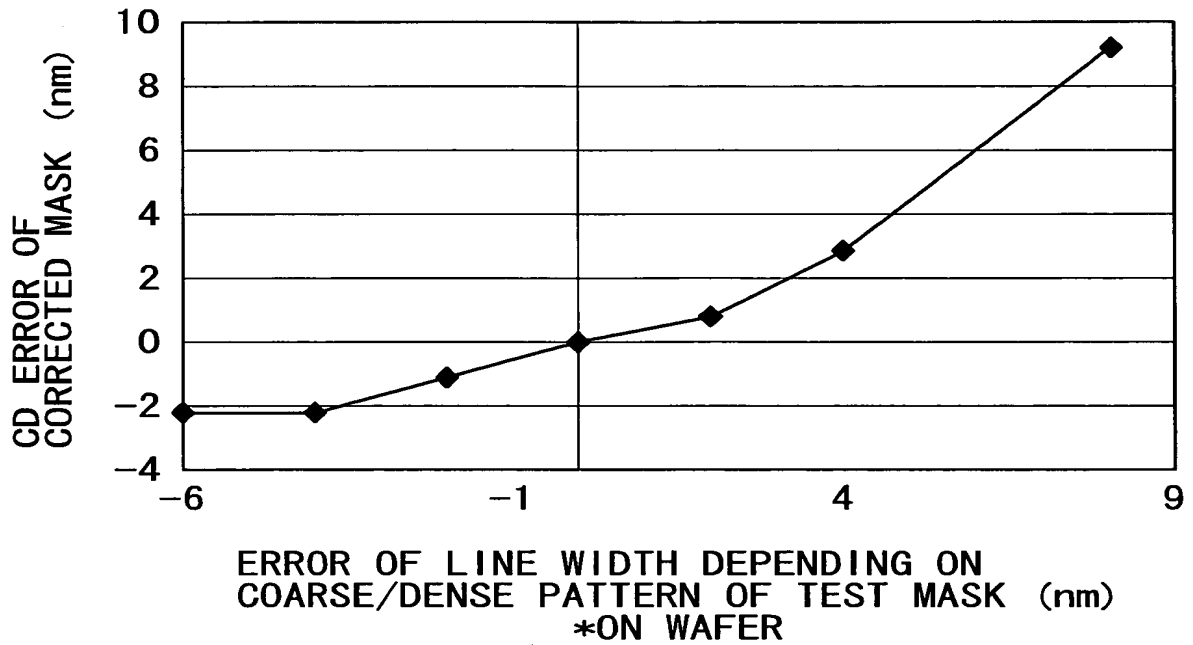


FIG. 4

DIMENSIONAL ERROR OF COARSE/DENSE MASK (ON W)	CALCULATED CORRECTED VALUE OF MASK	DIMENSIONS OF CORRECTED MASK (WHEN ERROR DEPENDING ON COARSE/DENSE IS REPRODUCED)	CD ERROR OF WAFER CD WHEN CORRECTED MASK IS TRANSFERRED
-6	132	126	-2.2
-4	130	126	-2.2
-2	128.5	126.5	-1.2
0	127	127	0
2	125.5	127.5	0.8
4	124.5	128.5	2.9
8	123.5	131.5	9.2

FIG. 5

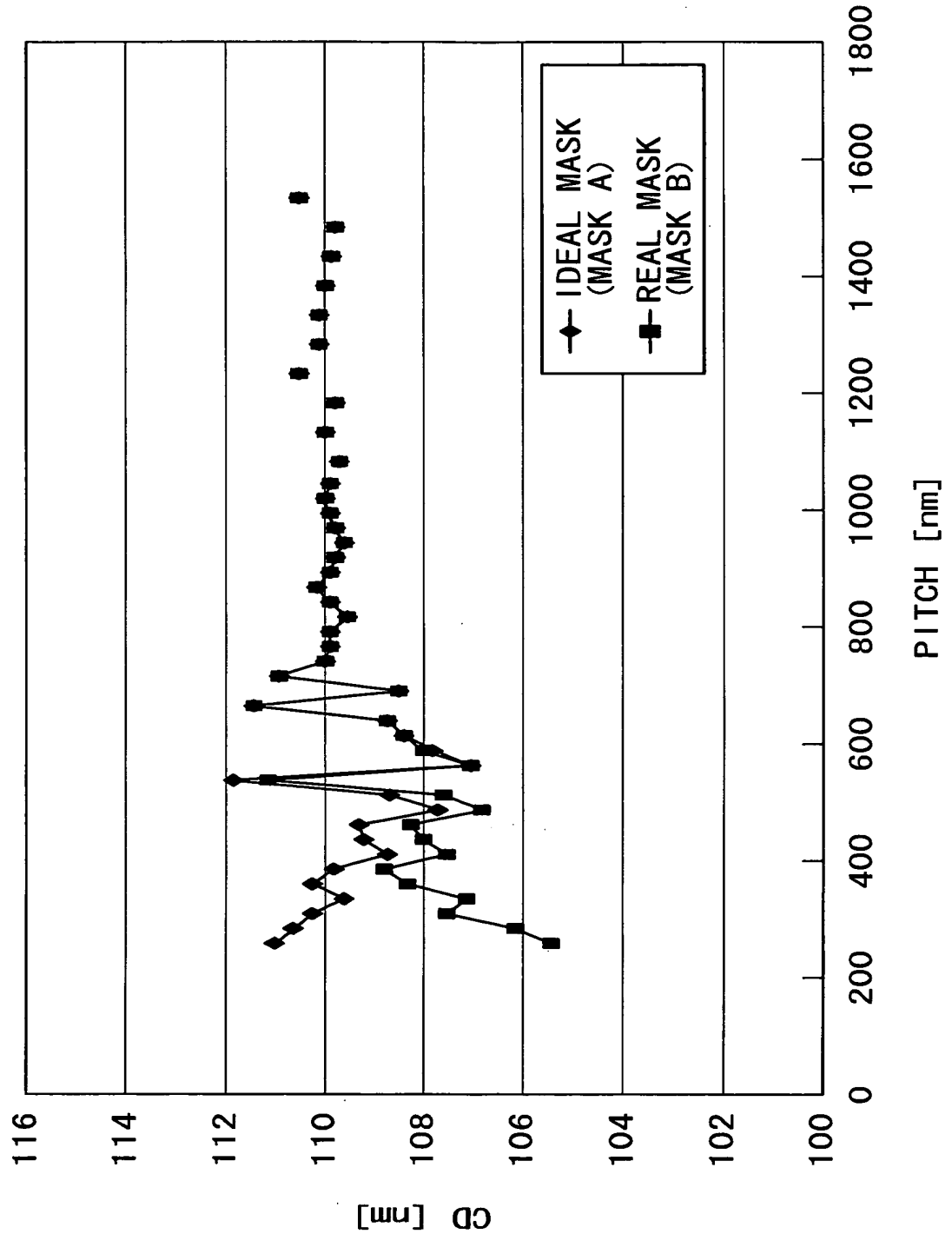


FIG. 6

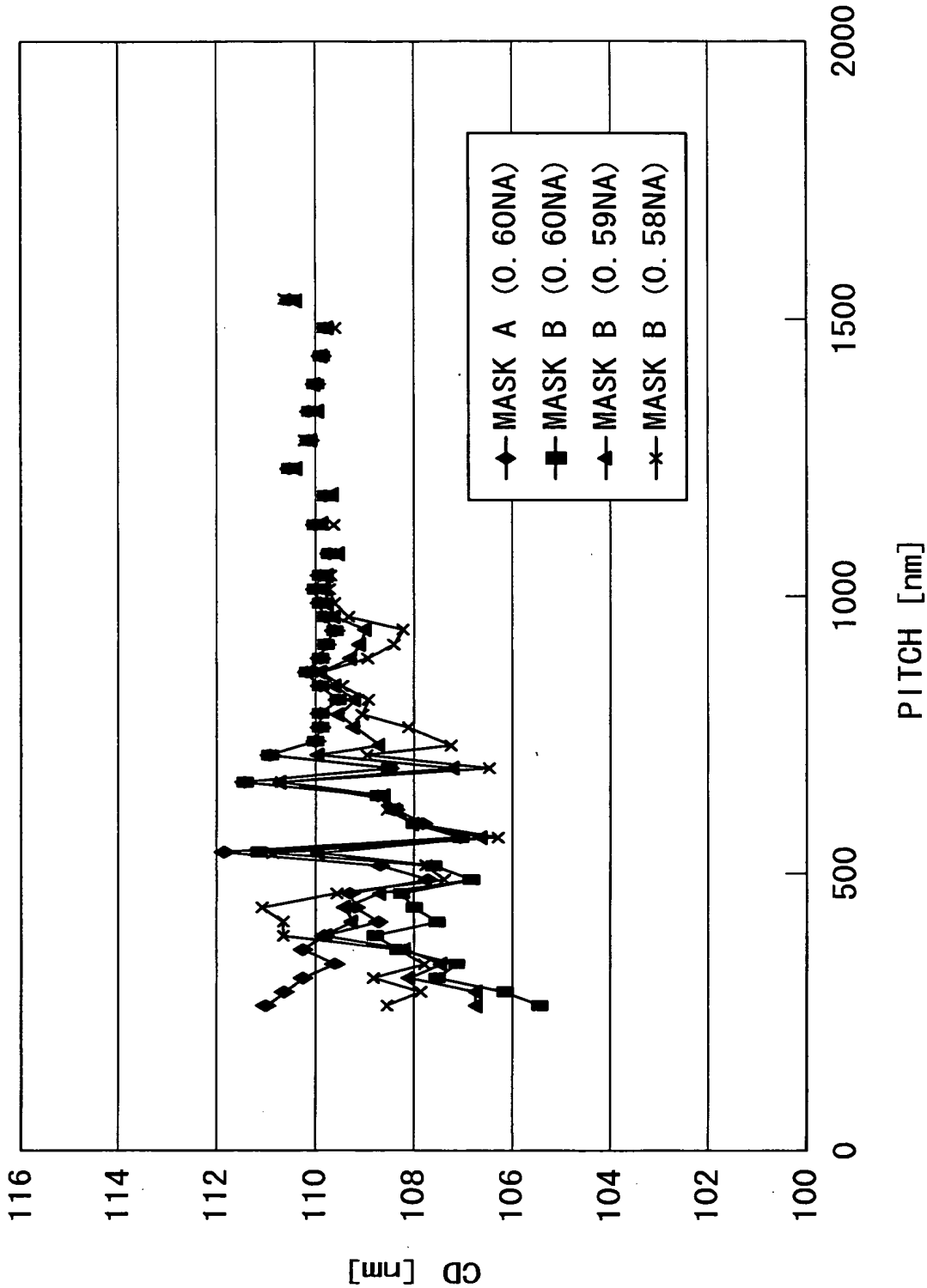


FIG. 7

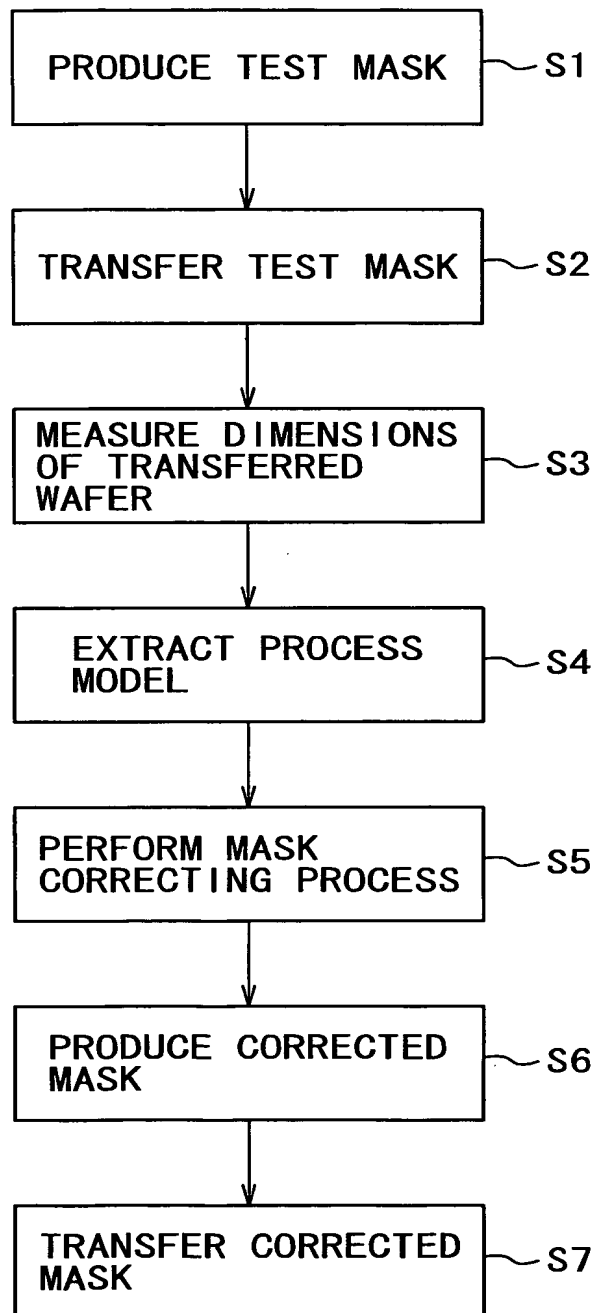


FIG. 8

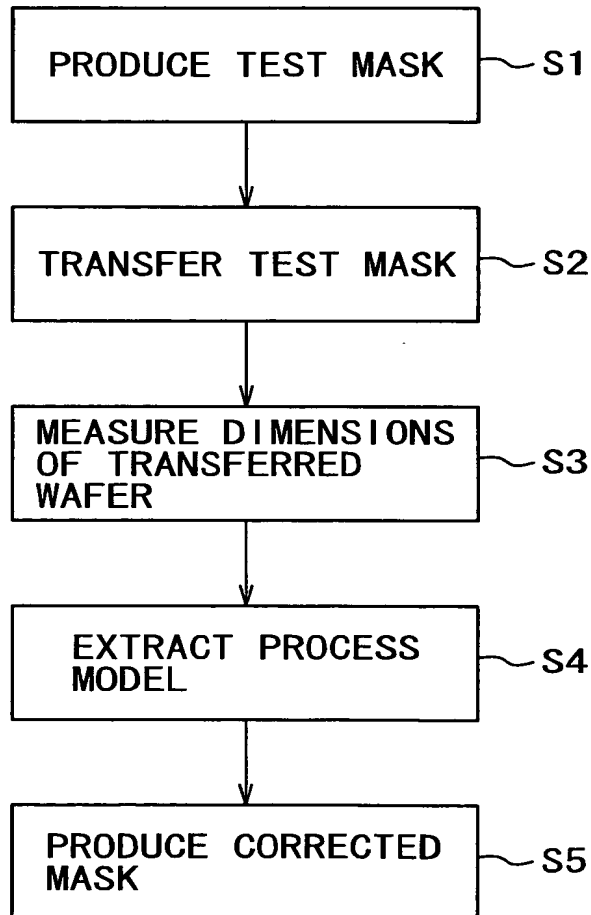


FIG. 9

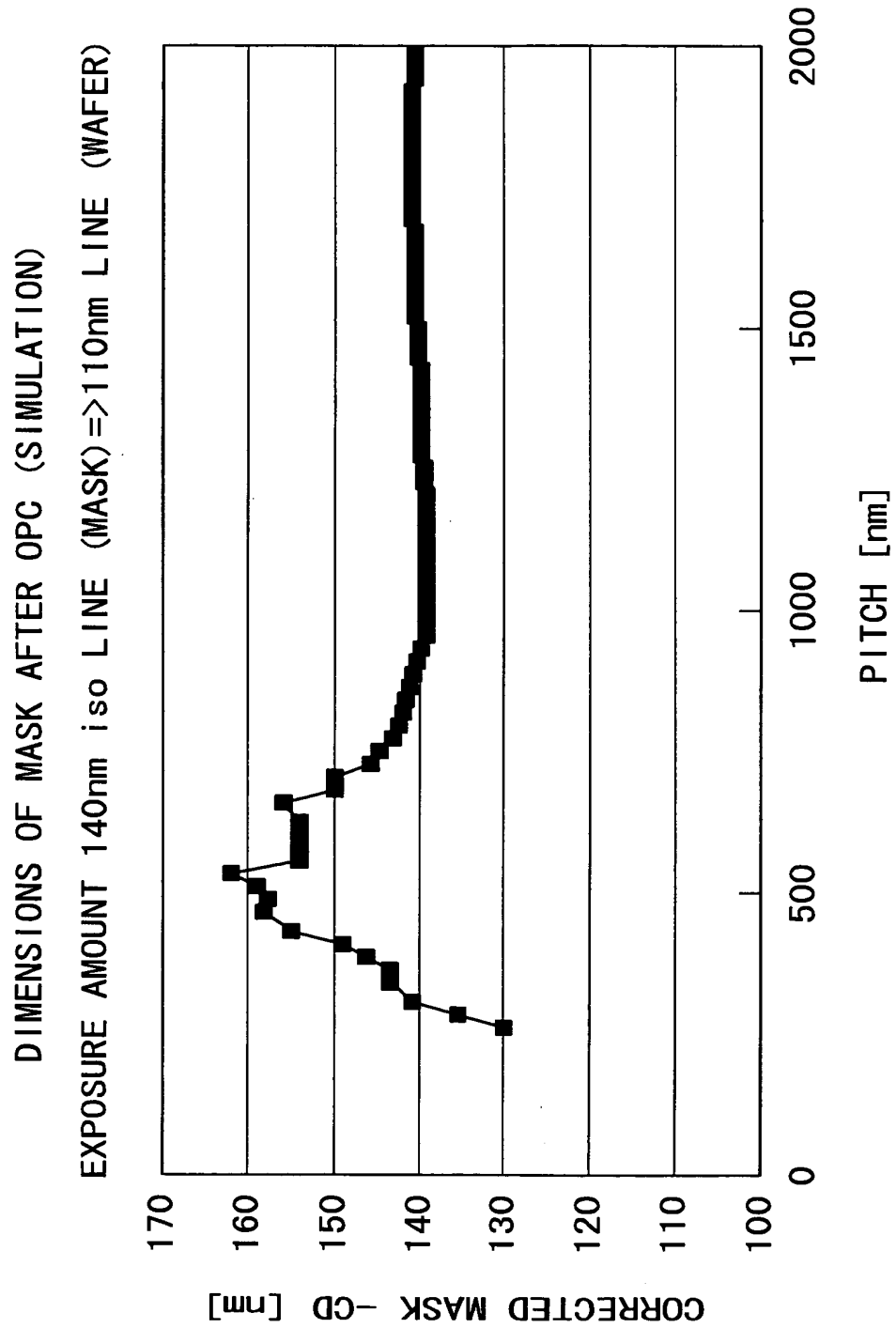


FIG. 10

ERROR OF LINE WIDTH DEPENDING ON
 COARSE/DENSE OF MASK B (ON WAFER)

(TARGET=140nm LINE, THROUGH-PITCH)

